

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18
Stylesheet Version v18.0

Title of Invention

APPARATUS FOR ELECTRO CHEMICAL DEPOSITION OF COPPER METALLIZATION WITH THE CAPABILITY OF INSITU THERMAL ANNEALING

Application Number:

10/686486

004

Confirmation Number:

8014

First Named Applicant:

ROBIN CHEUNG

Attorney Docket Number: AMAT3421C2

Art Unit:

1753

Search string:

(3649509 or 3727620 or 3770598 or 4027686 or 4092176 or 4110176 or 4113492 or 4315059 or 4326940 or 4336114 or 4376685 or 4405416 or 4428815 or 4435266 or 4489740 or 4510176 or 4518678 or 4519846 or 4568431 or 4693805 or 4732785 or 4789445 or 4816098 or 4816638 or 5039381 or 5055425 or 5069760 or 5092975 or 5100516 or 5155336 or 5162260 or 5222310 or 5224504 or 5230743 or 20010030101 or 20020000271 or 20020022363 or 20020029961

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

or 20020037641 or 20020074233).pn.

	init	Cite.No.	Patent No.	Date	Patentee		Class	Subclass
TAD) 1 3649509		1972-03-14	MORAWETZ, ET AL.			
		2	3727620	1973-04-17	ORR			
		3	3770598	1973-11-06	CREUTZ			•
		4	4027686	1977-06-07	SHORTES, ET AL.			
		5	4092176	1978-05-30	KOZAI, ET AL.		-	
		6	4110176	1978-08-29	CREUTZ, ET AL. (DECEASED)			
		7	4113492	1978-09-12	SATO, ET AL.			
		8	4315059	1982-02-09	RAISTRICK, ET AL.			
		9	4326940	1982-04-27	ECKLES, ET AL.			
	M	10	4336114	1982-06-22	MAYER, ET AL.			
ļſ	7					l		

APP ID=10686486 Page 1 of 3



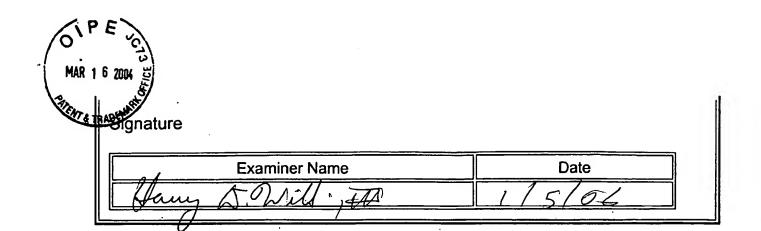
H	11	4376685	1983-03-15	WATSON
	12	4405416	1983-09-20	RAISTRICK, ET AL.
	13	4428815	1984-01-31	POWELL, ET AL.
\Box	14	4435266	1984-03-06	JOHNSTON
	15	4489740	1984-12-25	RATTAN, ET AL.
	16	4510176	1985-04-09	CUTHBERT, ET AL.
	´ 17	4518678	1985-05-21	ALLEN
	18	4519846	1985-05-28	AIGO
	19	4568431	1986-02-04	POLAN, ET AL.
	20	4693805	1987-09-15	QUAZI
	21	4732785	1988-09-15	QUAZI
	22	4789445	1988-12-06	GOFFMAN, ET AL.
	23	4816098	1989-03-28	DAVIS, ET AL.
	24	4816638	1989-03-28	UKAI, ET AL.
	25	5039381	1991-08-13	MULLARKEY
	26	5055425	1991-10-08	LEIBOVITZ, ET AL.
	27	5069760	1991-12-03	TSUKAMOTO, ET AL.
	28	5092975	1992-03-03	YAMAMURA, ET AL.
	29	5100516	1992-03-30	NISHIMURA, ET AL.
	30	5155336	1992-10-13	GRONET, ET AL.
	31	5162260	1992-11-10	LEIBOVITZ, ET AL.
	32	5222310	1993-06-29	THOMPSON, ET AL.
	33	5224504	1993-07-06	THOMPSON, ET AL.
th	34	5230743	1993-07-27	THOMPSON, ET AL.

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
HI	1	20010030101	2001-10-18	BERNER, ET AL.	,		
	2	20020000271	2002-01-03	RITZDORF, ET AL.			
	3	20020022363	2002-02-21	RITZDORF, ET AL.			
	4	20020029961	2002-03-14	DORDI, ET AL.			
	5	20020037641	2002-03-28	RITZDORF, ET AL.			
16	6	20020074233	2002-06-20	RITZDORF, ET AL.			

APP_ID=10686486





ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18 Stylesheet Version v18.0

Title of Invention

APPARATUS FOR ELECTRO CHEMICAL DEPOSITION OF COPPER METALLIZATION WITH THE CAPABILITY OF INSITU THERMAL ANNEALING

Application Number:

10/686486

Confirmation Number:

8014

First Named Applicant:

ROBIN CHEUNG

Attorney Docket Number: AMAT3421C2

Art Unit:

1753

Search string:

(2026605 or 4265943 or 4786337 or 5156731 or 5384284 or 5510216 or 5846598 or 5885749 or 5891513 or 5907790 or 5913147 or 5994675 or 6017777 or 6030208 or 6037257 or 6171922 or 6174388 or 6207937 or 6211495 or 6222164 or 6242349 or 6258223 or 6290833 or 6296906 or 6483081 or 6544338 or 5431700 or 6072163

or 6307184 or 6423947 or 6529686 or 6639189 or 20020004301 or 20020102837 or

20030045095).pn.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
44	1	2026605 1936-01-07		ANTISELL			
	2	4265943	1981-05-05	GOLDSTEIN, ET AL.			
\prod	3	4786337	1988-11-22	MARTIN			
	4	5156731	1992-10-20	OGASAWARA, ET AL.			
	5	5384284	1995-01-24	DOAN, ET AL.			
	6	5510216	1996-04-23	CALABRESE, ET AL.			
	7	5846598	1998-12-08	SEMKOW, ET AL.			
	8	5885749	1999-03-23	HUGGINS, ET AL.			
	9	5891513	1999-04-06	DUBIN, ET AL.			
\Box	10	5907790	1999-05-25	KELLAM			
m	g) 11 5913147 1999-06-15		DUBIN, ET AL.				

6	IPE	2
(+	IAR 1 6 2004	FICE S
PATE	ME TRADE	2

U	12	5994675	1999-11-30	BETHUNE, ET AL.
	13	6017777	2000-01-25	KIM, ET AL.
	14	6030208	2000-02-29	WILLIAMS, ET AL.
	15	6037257	2000-03-14	CHIANG, ET AL.
	16	6171922	2001-01-09	MAGHSOUDNIA
	17	6174388	2001-01-16	SIKKA, ET AL.
	18	6207937	2001-03-27	STODDARD, ET AL.
	19	6211495	2001-04-03	STODDARD, ET AL.
	20	6222164	2001-04-24	STODDARD, ET AL.
	21	6242349	2001-06-05	NOGAMI, ET AL.
	22	6258223	2001-07-10	CHEUNG, ET AL.
	23	6290833	2001-09-18	CHEN
	24	6296906	2001-10-02	STIMMELL, ET AL.
	25	6483081	2002-11-19	BATCHELDER
	26	6544338	2003-04-08	BATCHELDER, ET AL.
	27	5431700	1995-07-11	SLOAN
	28	6072163	2000-06-06	ARMSTRONG, ET AL.
	29	6307184	2001-10-23	WOMACK, ET AL.
	30	6423947	2002-07-23	WOMACK, ET AL.
	31	6529686	2003-03-04	RAMANAN, ET AL.
M	32	6639189	2003-10-28	RAMANAN, ET AL.

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
L	1	20020004301	2002-01-10	CHEN, ET AL.			
In-	2	20020102837	2002-08-01	RITZDORF, ET AL.			
NG	3	20030045095	2003-03-06	RITZDORF, ET AL.			

Signature

Examiner Name	Date		
Jany D. Will the	175/06		



ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18 Stylesheet Version v18.0

> Title of Invention

APPARATUS FOR ELECTRO CHEMICAL DEPOSITION OF COPPER METALLIZATION WITH THE CAPABILITY OF IN-SITU THERMAL ANNEALING

Application Number:

10/686486

Confirmation Number:

8014

First Named Applicant:

ROBIN CHEUNG

Attorney Docket Number: AMAT3421C2

Art Unit:

1753

Search string:

(5252807 or 5256274 or 5259407 or 5290361 or 5292393 or 5316974 or 5324684 or 5328589 or 5349978 or 5368711 or 5377425 or 5377708 or 5415890 or 5429733 or 5442235 or 5447615 or 5449447 or 5516412 or 5527739 or 5608943 or 5625170 or 5651865 or 5677244 or 5705223 or 5716207 or 5718813 or 5723028 or 5820692 or 5884009 or 6015749 or 6071388 or 6093291 or 6136163 or 6187152 or 6203582 or 6207005 or 6258220 or 6267853 or 6276072 or 6290865

or 6290933 or 6294059 or 6309520 or

6508920).pn.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

	init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
DW.		1	5252807	1993-10-12	CHIZINSKY			
1		2	5256274	1993-10-26	PORIS			
		3	5259407	1993-11-09	TUCHIDA, ET AL.			
		4	5290361	1994-03-01	HAYASHIDA, ET AL.			
		5	5292393	1994-03-08	· MAYDAN, ET AL.	•		
		6	5316974	1994-05-31	CRANK			
		7	5324684	1994-06-28	KERMANI, ET AL.			
		8	5328589	1994-07-12	MARTIN	•		
	HL	9	5349978	1994-09-27	SAGO, ET AL.			

OTHE 'S
MAR 1 6 2004
THE THE PROPERTY OF

Mul	10	5368711	1994-11-29	PORIS
V	11	5377425	1995-01-03	KAWAKAMI, ET AL.
	12	5377708	1995-01-03	BERGMAN, ET AL.
	13	5415890	1995-05-16	KLOIDER, ET AL.
	14	5429733	1995-07-04	ISHIDA
	15	5442235	1995-08-15	PARRILLO, ET AL.
	16	5447615	1995-09-05	ISHIDA
	17	5449447	1995-09-12	BRANDERS
	18	5516412	1996-05-14	ANDRICACOS, ET AL.
	19	5527739	1996-06-18	PARRILLO, ET AL.
	20	5608943	1997-03-11	KONISHI, ET AL.
	21	5625170	1997-04-29	PORIS
	· 22	5651865	1997-07-29	SELLERS
	23	5677244	1997-10-14	VENKATRAMAN
	24	5705223	1998-01-06	BUNKOFSKE
	25	5716207	1998-02-10	MICHINA, ET AL.
	26	5718813	1998-02-17	DRUMMOND, ET AL.
	27	5723028	1998-03-03	PORIS
	28	5820692	1998-10-13	BAECKER, ET AL.
	29	5884009	1999-03-16	OKASE
	30	6015749	2000-01-18	LIU, ET AL.
Ш	31	6071388	2000-06-06	UZOH
	32	6093291	2000-07-25	IZUMI, ET AL
Ш	33	6136163	2000-10-24	CHEUNG, ET AL.
	34	6187152	2001-02-13	TING, ET AL.
	35	6203582	2001-03-20	BERNER, ET AL.
Ш	36	6207005	2001-03-27	HENLEY, ET AL.
Ш	37	6258220	2001-07-10	DORDI, ET AL.
Щ	38	6267853	2001-07-31	DORDI, ET AL.
Ш	39	6276072	2001-08-21	MORAD, ET AL.
	40	6290865	2001-09-18	LLOYD, ET AL.
	41	6290933	2001-09-18	DURGA, ET AL.
	42	6294059	2001-09-25	HONGO, ET AL.
	43	6309520	2001-10-30	WOODRUFF, ET AL.
h	44	6508920	2003-01-21	RITZDORF, ET AL.

Signature

MAR 1 6 2004 3	
Examiner Name	Date
Jany D. Will , Ht	1/5/06

Approved for use through 07/31/2006, OMB 0651-0031
U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE ons are required to respond to a collection of information unless it displays a valid OMB control number.

Under the Paperwirk Reduction Act of 1995, to

APR 2 6 2004

Substitute for form 1449A/PTO

Examiner

SUPPLEMENT ALL INFORMATION DISCLOSURES STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet 1 of 2

orderio are required to respect to the extense		
Application Number	10/686,486	
Filing Date	OCT. 15, 2003	
First Named Inventor	CHEUNG, ET AL.	
Group Art Unit	1753	
Examiner Name	UNKNOWN	
Attorney Docket Number	AMAT/3421.C2/CMP/ECP/RKK	
Submission Date	APRIL 23, 2004	フ

	U.S. PATENT DOCUMENTS					
Examiner		Publication Date	Name of Patentee or	Pages, Columns, Lines, Where		
Initials*	No.1	Number-Kind Code ^{2 (F known)}	MM-DD-YYYY		Relevant Passages or Relevan Figures Appear	
• • • • • • • • • • • • • • • • • • • •	A1	US-				
	A2	UŞ-				
	A3	US-				
	A4	US-				
.,	A5	US-				
	A6	UŞ-				
	A7	US-				
	A8	US-				
	A9	US-				

		FORE	IGN PATENT I	DOCUMENTS		
Examiner Cite	Cite	Foreign Patent Document	Publication Date	Name of Patentee or	Pages, Columns, Lines,	T⁰
initiais	No.	Country Code ³ -Number ⁴ -Kind Coode ⁵ (if known)	MM-DD-YYYY	Applicant of Cited Document	Where Relevant Passages or Relevant Figures Appear	
HW	B1	EP 0 421 735 A2	04/10/1991	KABUSHIKI KAISHA TOSHIBA		
	B2	EP 0 881 673 A2	12/02/1998	INTERNATIONAL BUSINESS MACHINES CORPORATION		
	В3	EP 1 037 263 A2	09/20/2000	APPLIED MATERIALS, INC.		
	B4	EP 1 085 557 A2	03/21/2001	APPLIED MATERIALS, INC.		
	B5	JP 4-131395	05/06/1992			
	B6	JP 4-280993	10/06/1992			
	87	JP 54-148112 W/ENG. ABSTRACT	11/20/1979	NAKAGAWA KK		
	B8	JP 58-182823 W/ENG. ABSTRACT	10/25/1983	NIPPON DENKI KK .		
	B9	JP 6-17291 W/ENG. ABSTRACT	01/25/1994	NEC CORP		
	B10	JP 63-118093	05/23/1988	TANAKA ELECTRON INC		
$\overline{\mathbf{I}}$	B11	WO 97/12079	04/03/1997	INTEL CORPORATION		
pr	B12	WO 99/40615	08/12/1999	SEMITOOL, INC.		
	B13					

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. Applicant's unique citation designation number (optional). 2 See Kinds Codes of USPTO Patent Documents at www.uspto.gov or MPEP 901.04. 3 Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). A For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. Skind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. Applicant is to place a check mark here if English tanguage Translation is attached.

Date Considered

This collection of information is required by 37 CFR 1.97 and 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450. If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-786-9199) and select option 2.

Please	hma	2 0	hie	sinn	/+1	insida	this	hax
riodso	17 PO	σμ	140	DIMI	'''	HIGHUO		~~

PTO/SB/08b (08-03) Approved for use through 06/30/2008. OMB 0651-0031 U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE
of a collection of information unless it displays a valid OMB control number.

Substitute for form 1449B/PTO

SUPPLEMENTAL INFORMATION DISCE STATEMENT BY APPLIC

(Use as many sheets as necessary)

Sheet	2	of	2

ersons are required to respond to a collec-	HOT OF INIONIATION UNITESS IT O'S PLAYS A VAIRU ONES CONTROL THEFT	IU6
Application Number	10/686,486	1
Filing Date	OCT. 15, 2003	
First Named Inventor	CHEUNG, ET AL.	
Group Art Unit	1753	
Examiner Name	UNKNOWN	
Attorney Docket Number	AMAT/3421.C2/CMP/ECP/RKK	
Submission Date	'APRIL 23, 2004	J

Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the	
110.	item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
	COLOMBO, Wafer Back Surface Film Removal, Central R&D, SGS-Thomson Microelectronics, Agrate, Italy, Spin Tech Technology, 6 pages.	
	Semitool Products/Sales from www.Semitool.com Metallization and Interconnect, October 27, 1998, 4 pages.	
	Verteq from www.verteq.com Welcome to Verteq Online Products Overview, 5 pages.	
	Technologies Corporation from www.laurell.com, 6 pages.	
	SINGER, Nonuniformity of Copper Electroplating Studied, Wafer Processing, Semiconductor International. June 1998, page 70.	
	Tantalum, Copper and Damascene: The Future of Interconnects, Semiconductor International, June 1998, pages 91-98.	
	PITNEY, Ney Contact Manual, Electrical Contacts for Low Energy Uses, October 8, 1974, 19 pages.	
-	HOLM, Electric Contacts Theory and Application, Fourth Completely Rewritten Edition, Springer-Verlag, New York Inc., August 21, 1967, 27 pages.	
	·	
	· · · · · · · · · · · · · · · · · · ·	Semitool Products/Sales from www.Semitool.com Metallization and Interconnect, October 27, 1998, 4 pages. Verteq from www.verteq.com Welcome to Verteq Online Products Overview, 5 pages. Technologies Corporation from www.laurell.com , 6 pages. SINGER, Nonuniformity of Copper Electroplating Studied, Wafer Processing, Semiconductor International. June 1998, page 70. Tantalum, Copper and Damascene: The Future of Interconnects, Semiconductor International, June 1998, pages 91-98. PITNEY, Ney Contact Manual, Electrical Contacts for Low Energy Uses, October 8, 1974, 19 pages. HOLM, Electric Contacts Theory and Application, Fourth Completely Rewritten

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. 1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.

This collection of information is required by 37 CFR 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an In soluction of information is required by 37 CFR 1.36. The information is required to obtain or retain a benefit by the public which is a line (and by the CSFI O in process) application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated to take 2 hours to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depending upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden, should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, P.O. Box 1450, Alexandria, VA 22313-1450. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450. If you need assistance in completing the form, call 1-800-PTO-9199 (1-800-786-9199) and select option 2.